Silicon Nitride Corrugated Membrane with High-Width-Aspect-Ratio for MEMS

Microphones

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INTRODUCTION: In this work, the corrugated membrane design with focus on the corrugation width to improve the acoustic sensitivity of the micro-machined silicon MEMS microphones has been presented. Finite Element Modeling approach and analytical analyzes have been carried out to optimize the acoustic sensitivity of the corrugated membrane. The measurement shows very good agreement with the simulated values using FEM. Acoustic sensitivity as high as 13.4nm/Pa, can be achieved with 65um corrugation width at 220MPa of initial silicon nitride stress for N=3 corrugations, for a given diaphragm thickness, 1.1um and corrugation height, 3.5um.

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 $S_{3} = -(1e - 7) \cdot w_{c}^{4} + (7e - 5) \cdot w_{c}^{3} - (0.0114) \cdot w_{c}^{2} + 0.7084 \cdot w_{c} - 1.4439$

where, S_1 , S_2 and S_3 are acoustic sensitivity of the 1, 2 and 3 number of corrugations, respectively and w_c is the corrugation width

2D and 3D models have been implemented using Structural Mechanics module of the COMSOL Multiphysics[®] simulation software. The analytical expression is represented as mentioned.

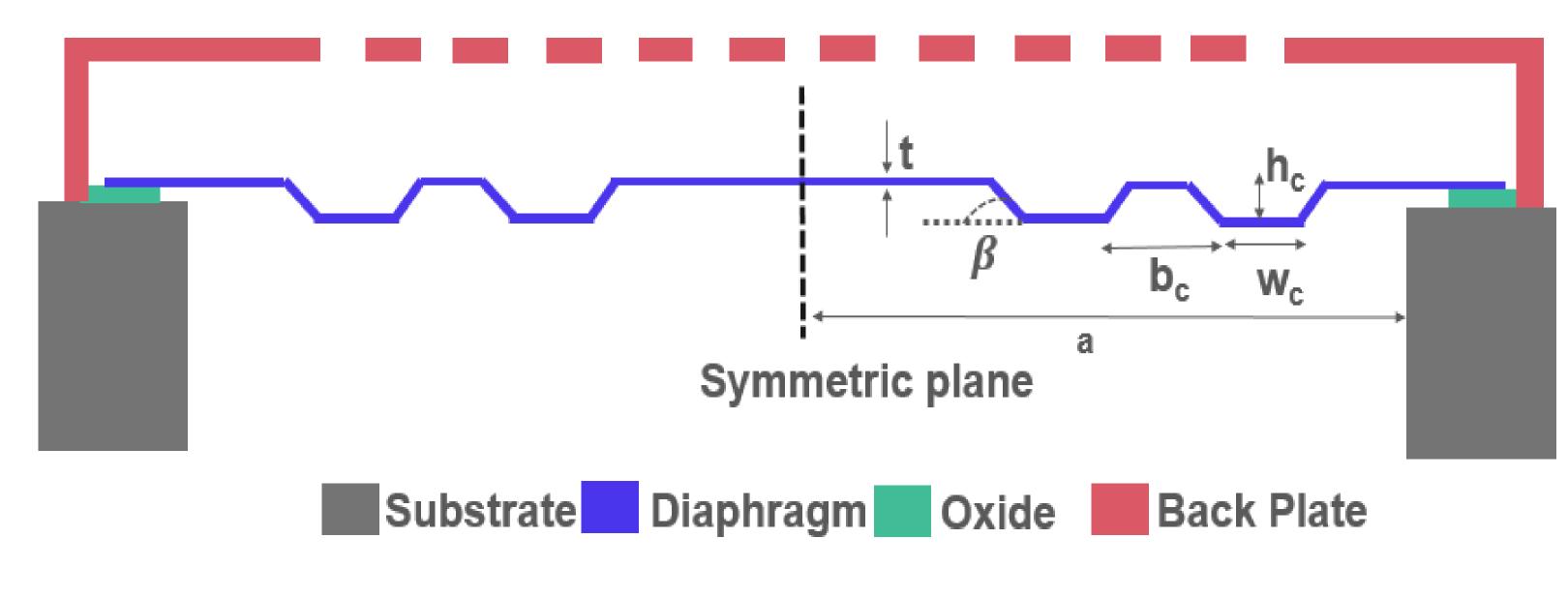
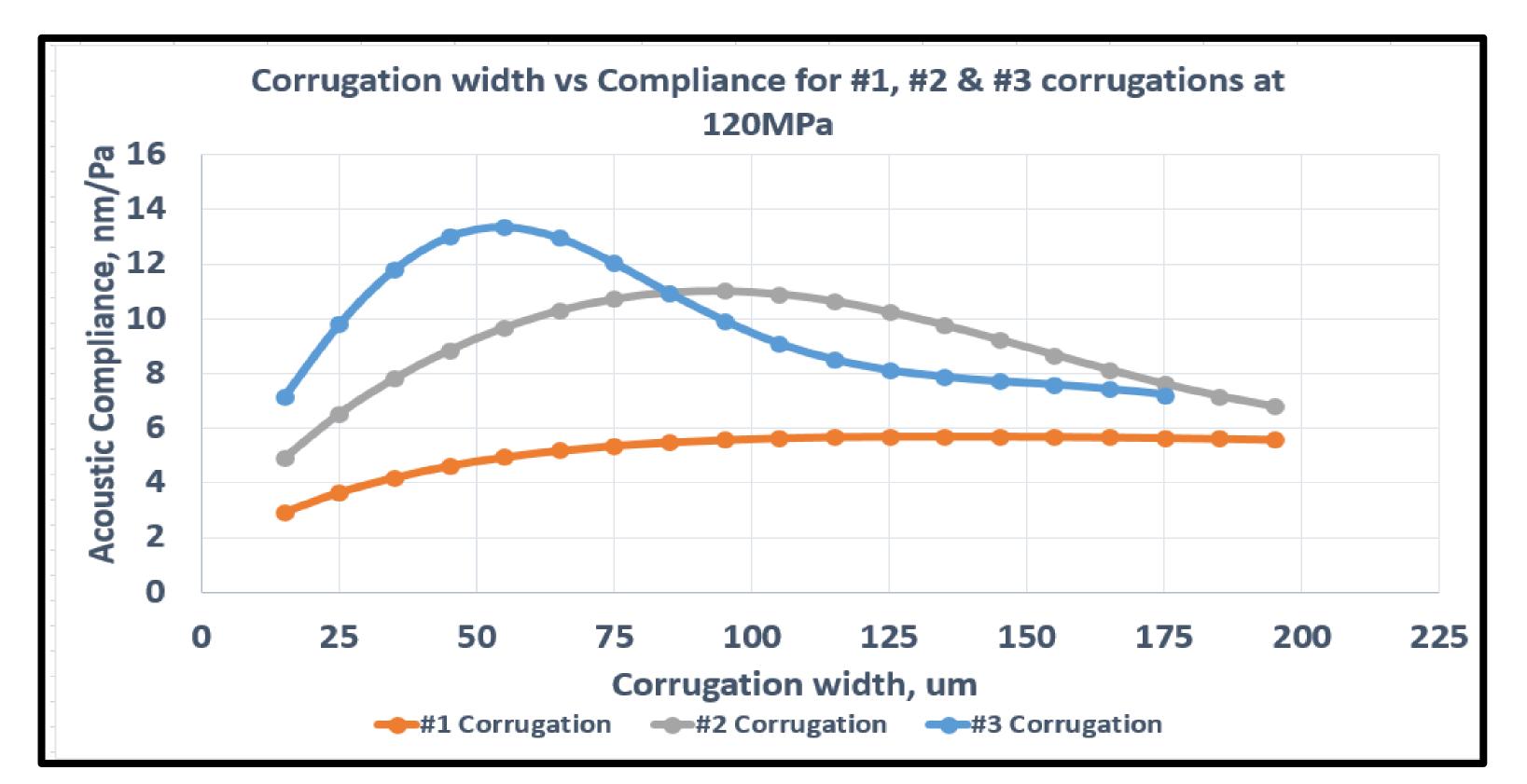


Figure 1. Cross-section schematic representation of corrugated membrane MEMS microphone

Table 1. Geometry and Material Properties

Parameters	Value	Distance from constrained region	70um
Diaphragm Radius, a	700 um	to first corrugation	
Diaphragm material	Silicon Nitride	Sacrificial oxide thickness	1.5um
Diaphragm Thickness, t	1.1um	Sacrificial oxide initial stress	100 MPa (compressive)
Corrugation Height, h_c	3.5um	Density (Silicon Nitride)	3100 [kg/m^3]
Number of Corrugations, N _c	1, 2 and 3	Young`s modulus (Silicon	250e9 [Pa]
Wall angle, β	60°	Nitride)	
Distance between two	30um	Poisson`s ratio (Silicon Nitride)	0.23
corrugations, b_c		Density (Sacrificial Oxide)	2200 [kg/m^3]
confugations, <i>b_c</i>		Young`s modulus (Sacrificial	70e9 [Pa]
		Oxide)	
RESULTS :		Poisson`s ratio (Sacrificial Oxide)	0.17



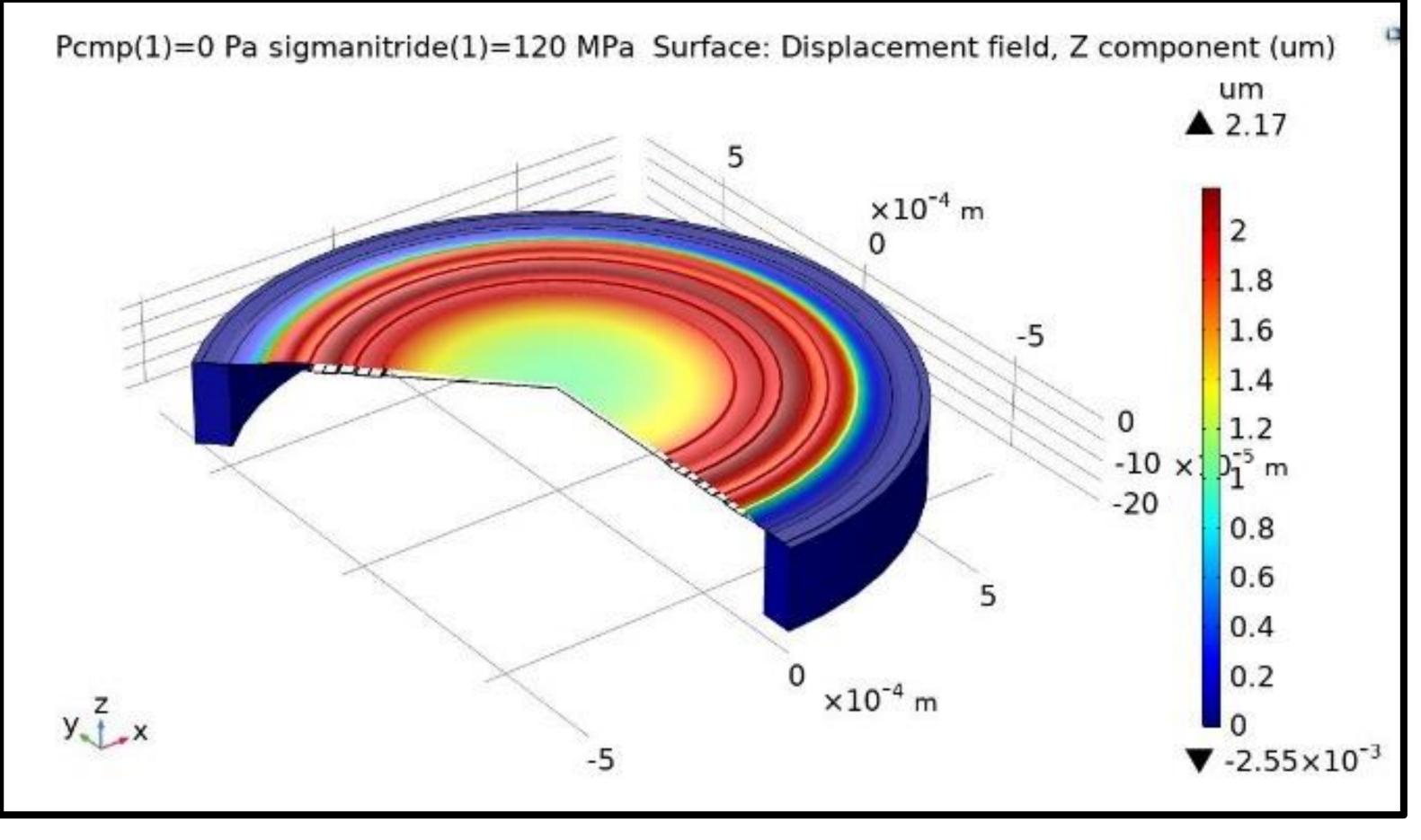


Figure 2. 3D deflection profile of corrugated membrane with initial stress if silicon nitride as 120MPa and N_c = 3 corrugations

COMPUTATIONAL METHODS:

Figure 2. Acoustic compliance vs corrugation width for 120MPa of initial silicon nitride stress with N_c = 1, 2 and 3 corrugations

 Table 2. Microphone Acoustic Compliance

	#1 Corrugation		#2 Corrugations		#3 Corrugations	
Corrugation width	15um	35um	15um	35um	15um	35um
Simulated (nm/Pa)	1.45	1.86	2.5	3.74	3.73	6.1

Acoustic Sensitivity = $\frac{\text{Center Deflection, m}}{\text{Sound Pressure, Pa}}$

$$S(circular) \approx \frac{R^2}{8.t.\sigma_0} \cdot \left(\frac{2.E.t^2}{(1-\vartheta^2).\sigma_0.R^2} + 1\right)^{-2}$$

 $C_{corrugated} = C_{circular}(\sigma_0).$

$$(1 + 6. \sin\beta \cdot \frac{h_c^2}{t^2} \cdot N_c \cdot \frac{w_c}{R - N_c \cdot (w_c + b_c)})$$

$$S_1 = (1e - 6) \cdot w_c^3 - (6e - 4) \cdot w_c^2 + 0.0818 \cdot w_c + 1.9228$$

$$S_2 = (4e - 6) \cdot w_c^3 - (0.0018) \cdot w_c^2 + 0.2324 \cdot w_c + 1.7295$$

Experimental (nm/Pa)	1.47	1.75	2.3	3.7	3.7	5.8

CONCLUSIONS:

The measurement shows very good agreement with simulated values at 220MPa of initial silicon nitride stress and can help to optimize acoustic sensitivity to boost sensor performance.

REFERENCES:

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[2] M. Fuldner, A. Dehé, and Reinhard Lerch, "Analytical Analysis and Finite Element Simulation of Advanced Membranes for Silicon Microphones", *IEEE Sensors Journal*, vol. 5, no. 5, pp. 857-863, 2005.